Form PTO 1449		U.S. DEPARTMENT OF		ATTY DOCKET NO. 247866US2S		SERIAL NO. New Application			
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LIST OF	REFER	RENCES CITED BY APPL	JCANT	Akira HOKAZONO, et al.					
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OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)									
amy	ΑW	A.S.W. WONG, et al., "Enhanced Thermal Stability of NiSi Films on 20KEV BF <sub>2</sub> + Implanted (100) Si", SYMPOSIUM B SILICON MATERIAL-PROCESSING, CHARACTERIZATION AND RELIABILITY, MRS 2002 Spring Meeting, April 1-5, 2002, 1 Page							
411	AX	T. OHGURO, et al., "Analysis of Anomalously Large Junction Leakage Current of Nickel Silicided N-Type Diffused Layer and its Improvement", EXTENDED ABSTRACTS OF THE 1993 INTERNATIONAL CONFERENCE ON SOLID STATE DEVICES AND MATERIALS, 1993 Pages 192-194							
	AY	DE VIOLO RICHIERIALO, 1990 Fages 192-194							
	AZ					Additional References sheet(s) attached			
Examiner	L	Jane Wager				Date Considered 0 3 2 1 3 5			
*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.									